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Fees
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495885 -- Patent Information

Published Serial No.	**495885**
Title	**Method and apparatus for processing a microelectronic workpiece at an elevated temperature**
Patent type	B
Date of Grant	2002/7/21
Application Number	090102866
Filing Date	2001/2/9
IPC	H01L21/324
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Priority	

Country	Application Number	Priority Date
	US20000501002	2000/02/09
	US20000733608	2000/12/08

Applicant

Name	Country	Individual/Company
SEMITOOL, INC.	US	Company

Abstract	An apparatus and method for processing a microelectronic workpiece at an elevated temperature. In one embodiment, the apparatus includes a workpiece support positioned to

	engage and support the microelectronic workpiece during operation. The apparatus can further include a heat source having a solid engaging surface positioned to engage a surface of the microelectronic workpiece with at least one of the heat source and the workpiece support being movable relative to the other between a first position with the microelectronic workpiece contacting the engaging surface of the heat source and a second position with the microelectronic workpiece spaced apart from the engaging surface. The heat source is sized to transfer heat to the microelectronic workpiece at a rate sufficient to thermally process a selected material of the microelectronic workpiece when the microelectronic workpiece is engaged with the heat source. A heat sink can be positioned at least proximate to the heat source to cool both the heat source and the microelectronic workpiece.